

ABSTRACT OF THE DISCLOSURE

ETCHING SOLUTION FOR TUNGSTEN WORD LINE RECESS

Described herein is an etching solution suitable for both tungsten-containing metals and TiN-containing materials, which comprises: water; and one or more than one oxidizers; and one or more than one of the components selected from the group consisting of: one or more fluorine-containing-etching compounds, one or more organic solvents, one or more chelating agents, one or more corrosion inhibitors and one or more surfactants.

[no figure]